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PATENT ABSTRACTS OF JAPAN

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(54) RADIATION SENSITIVE RESIN COMPOSITION

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain a resin compsn, almost independent of stationary waves, excellent in focus latitude and useful as a chemical amplification type resist excellent in balance of characteristics including sensitivity, resolution, pattern shape and process latitude.

SOLUTION: This resin compsn. contains a polymer having functional groups each selected from among substituents separately having an acid-degradable acetal group, an acid-degradable ketal group and an acid-degradable t-butyl group, a radiation sensitive acid generating agent and a compd. having a functional group selected from among a phenolic hydroxyl group, an alcoholic hydroxyl group and an ethylene oxide chain and having a mol.wt. of $\leq 1,000$.

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